VERTEX 2012, Jeju

Fast, granular and ultra-light pixelated double sided ladders based on CMOS sensors for an ILC vertex detector adapted to the ultimate collision energy

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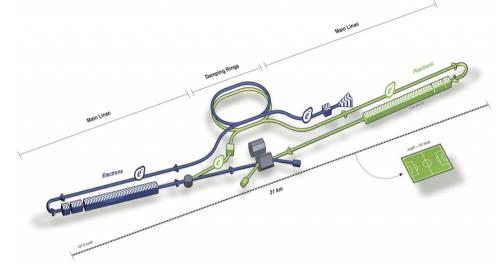


Outline

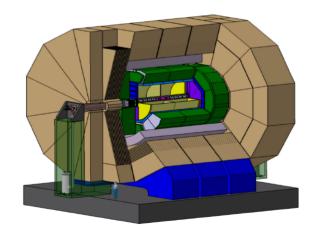
- ILD Vertex Detector (VXD)
 - Physics motivation & requirements
- CMOS baseline architecture
- CMOS sensors based VXD
 - > Design for \sqrt{s} = 500 GeV
 - Inner layer sensors
 - Outer layers sensors
 - > Design for $\sqrt{s} = 1$ TeV
 - Moving to 0.18 µm CMOS technology
 - MIMOSA 32 test beam results
- Conclusions perspectives

ILC & ILD

- Future linear e⁺e⁻ collider, √s = 500 GeV 1 TeV
- Main motivations
 - Study of EWSB
 - Search and detailed study of new physics



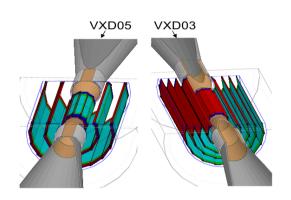
- 2 general purpose detectors, ILD & SiD
 - Letter of Intent (LoI) delivered in 2010
 - Detector Baseline Document (DBD) under preparation
 - To be delivered by the end of 2012

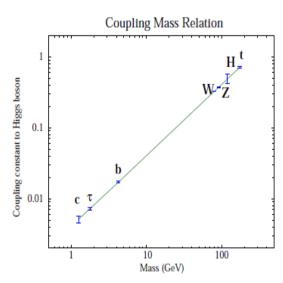


Japanese HEP community approved ILC (August 2012)

VXD physics motivations

- Excellent "heavy" flavour tagging
- Standalone track reconstruction (low mom. tracks)





ILC expected sensitivity

- Prominent example: measurement of the Higgs couplings
 - Requires excellent flavour tagging capabilities (b, c, τ)
 - Main challenge, tag c hadrons (cτ ~ O(100 μ m)) and τ leptons (cτ = 87 μ m)
 - ★ Required Impact Parameter (IP) resolution ~ 10 μm

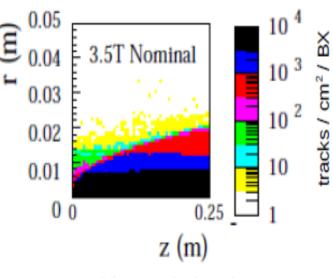
$\sigma_{IP} =$	a	\oplus	b/p	, ·	$\sin^{\frac{3}{2}}$	(θ)
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- a ≤ 5 μm
- b ≤ 10 µm GeV / c

Accelerator	$a~(\mu \mathrm{m})$	$b~(\mu \text{m}{\cdot}GeV/c)$
LEP	25	70
SLC	8	33
LHC	12	70
RHIC-II	13	19
ILD	< 5	< 10

VXD Requirements

- ILD physics program needs sensors
 - Highly segmented (s.p. resolution ~ 3 μm)
 - \rightarrow Thin (ladder X/X₀ in the per mill level)
 - Low power consumption → less complex cooling strategy
- ILC running conditions impose also certain requirements
- Dictated by the beam induced background (e⁺e⁻ pairs)
 - Swift readout
 - > O(10 μs) for the innermost, O(100 μs) for the outer layers
 - Moderate radiation tolerance
 - Expected 150 kRad, 10^{11} n_{eq}/cm² per year, sf 3

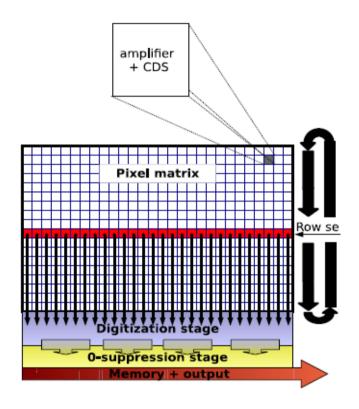


Beam bkg track density

CMOS sensors is a candidate technology that can fulfill the VXD specifications

MIMOSA sensors baseline architecture

- Baseline architecture: rolling shutter approach
 - Only the selected row is switched on
 - ★ Power saving!
 - Column parallel read-out, in pixel amplification & CDS
 - Column level discriminator + 0 suppression in sensor periphery
 - Integration time ~ to number of pixels / column
- Example: MIMOSA 26
 - Full scale digital sensor with integrated sparsified output
 - 1152 columns x 576 rows of 18.4 μm pitch pixels
 - Thinned down to 50 μm
 - 2 cm² 660k pixels
 - → 100 µs read-out
 - → ~ 3 3.5 µm spatial resolution (charge sharing)
 - AMS 0.35 μm fabrication process (high resistivity)
 - Developed to equip the EUDET beam telescope



Challenges

- ILD sensors requirements are in the physics dominated area
- But beam bkg → swift readout @ innermost layer

* Challenge

Swift readout while preserving spatial resolution

★ Conflict

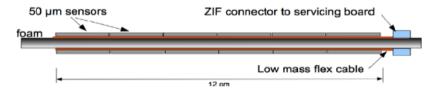
- Spatial resolution → high segmentation
- **→** Time resolution → low number of channels
- MIMOSA sensors offer genuinely
 - High spatial resolution &
 - Low material budget
- R & D effort focus on running constraints requirements

Towards 10 µs readout time

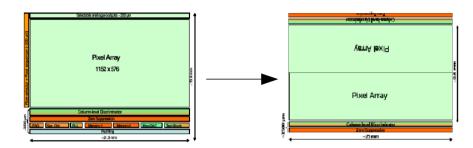
- How can we go from 100 to 10 μs readout time?
- Reduce the number of pixels / column
 - Apply a double sided readout
 - The insensitive area is double but
 - Going to smaller feature size CMOS technology → decrease of the overall insensitive area

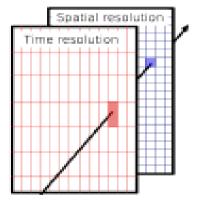


- Correlate hits of the same, traversing, particle on both surfaces (2 mm distant)
- Double sided ladders
 - Investigated by PLUME collaboration



- First prototype with 0.6 % X₀ (6 MIMOSA 26 per side) properties tested in 2011 (mechanical, electrical, cooling)
- > Second prototype tests $(0.35 \% X_0)$ foreseen for late 2012





CMOS based VXD – proposal for $\sqrt{s} = 500$ GeV

- Adopt rolling shutter approach
- Discrimination & data sparsification @ sensor's periphery
 - Inner layers → priority to spatial resolution and readout speed
 - One face: highly segmented digital square pixels sensors 16x16 μm²
 - ★ Spatial resolution < 3 µm</p>
 - Other face: elongated pixels in column direction 16x80 μm²
 - ★ Time resolution ~ 10 µs
 - Outer layers → priority to power saving
 - Larger pixels 34x34 μm² → reduced power dissipation, data flow
 - Columns ended with 3-4 bits ADCs
 - ★ Expected spatial resolution ~ 3.5 μm
 - Average power consumption of whole VXD < 15 W
 - Compatible with moderate air flow cooling
 - > Take advantage of the beam time structure 2 % duty cycle
- Three different sensors
 - Inner layer: square & elongated pixels (MIMOSA 30)
 - Outer layers: large pitch pixels (MIMOSA 31)

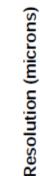
layer	σ _{spatial} (μm)	σ_{time} (µs)
L1	3/6	50 / 10
L2	4	100
L3	4	100

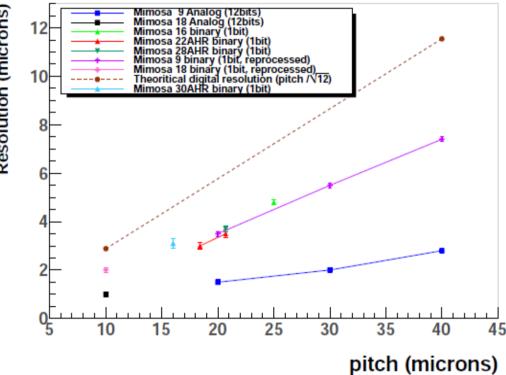
Feasible today with 0.35 µm process

Spatial resolution

Spatial resolution as a function of pixel pitch







- Resolution study of elongated pixels
 - MIMOSA 22 AHR
 - Pixel's dimensions 18.4 x 73.6 μm²
 - Digital output
 - ~ 6 μm spatial resolution in each direction

CMOS based VXD – proposal for $\sqrt{s} \ge 1$ TeV

- $\sqrt{s} \ge 1 \text{ TeV} \rightarrow \text{occupancy due to beam bkg increased} \sim 3-5 \text{ times}$
- To account for uncertainties in beam bkg simulations
 - Increase the readout speed of the VXD layers —

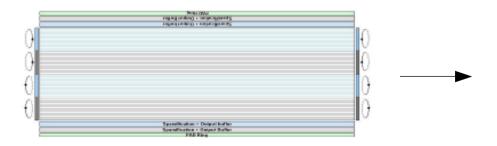
How can we	further	improve	readout?
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layer	σ _{spatial} (μm)	σ_{time} (µs)
L1	3/6	50 / 2
L2	4 / 10	100 / 7
L3	4 / 10	100 / 7

- Move to 0.18 µm process
- <u>In-pixel discriminator</u>
 - Don't have to drive the digital signal to the column end
 - Gain a factor of 2 in time resolution
 - 2 -4 rows readout simultaneously
 - Multiple rolling shutters



- More conservative approach
- Fit in 22 μm wide column
- Readout of $\sim 5 \mu s$ can be achieved
- Feasible with 0.35 μm technology
 - > Small ins. area in fiducial volume



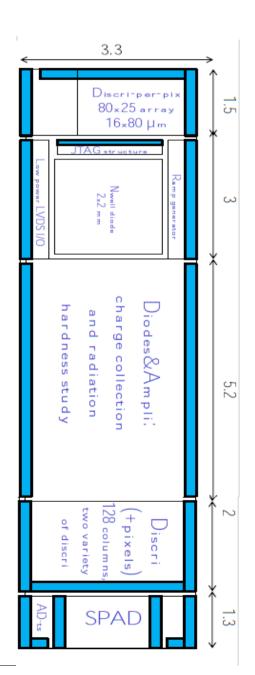
More rows switched on → higher power consumption: **but**

- → 0.18 µm process offers reduced power dissipation
- → Still complies with a passive cooling system

time resolution < 2 μs can be achieved</p>

0.18 µm prototype sensor

- Scope of MIMOSA 32: exploration of 0.18 µm process
 - → High res. epi layer (1 → 5 kΩ · cm)
 - > Quadruple well (deep P-wells hosting PMOS transistors)
 - 4 metal layers
- Various pixel designs
 - Squared or elongated pixels (with 1 or 2 charge coll. diodes)
 - Pixel matrices with column level discr.
 - ▶ In pixel discriminators
- Future steps
 - MIMOSA 32ter
 - In pixel amplifier + discriminator + 6 ML
 - Submitted July 2012
 - MIMOSA 22 THR (ALICE ITS upgrade prototype)
 - Full analog chain + 2 discr. / column
 - > 128 columns readout in parallel (1 cm long)
 - \rightarrow 8 10 diff. in pixel amplifiers
 - AROM 1
 - ✓ In pixel discr, 4 rows read out simultaneously
 - Submission: 2013

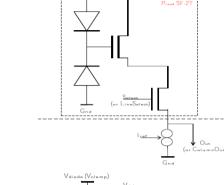


MIMOSA 32 test beam results

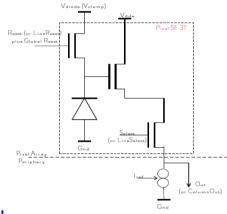
 $T = 15^{\circ}C$

Pixel design	Irradiation	S/N	Efficiency (%)
P1	0	35.1 ± 0.4	99.97 ± 0.03
P1	1 MRad + 10^{13} n_{eq}/cm^2	25.4 ± 0.3	99.67 ± 0.12
P6	0	32.3 ± 0.4	99.84 ± 0.07
P6	1 MRad + 10^{13} n_{eq}/cm^2	22.3 ± 0.3	99.87 ± 0.08
P9	0	30.9 ± 0.4	99.91 ± 0.06
P9	1 MRad + 10^{13} n_{eq}/cm^2	22.6 ± 0.4	99.92 ± 0.08
L4_1	0	22.6 ± 0.2	99.86 ± 0.06
L4_1	1 MRad + 10^{13} n_{eq}/cm^2	13.9 ± 0.3	99.51 ± 0.25
L4_2	0		
L4_2	1 MRad + 10^{13} n_{eq}/cm^2	13.3 ± 0.2	99.0 ± 0.2

• P1 (SB) →



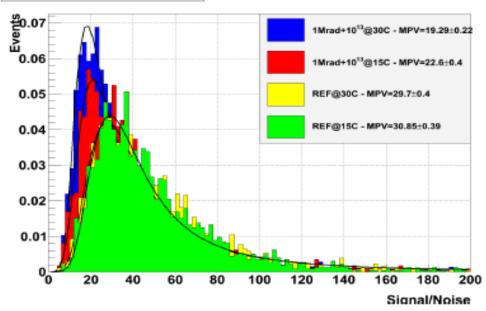
P6 (3T) →



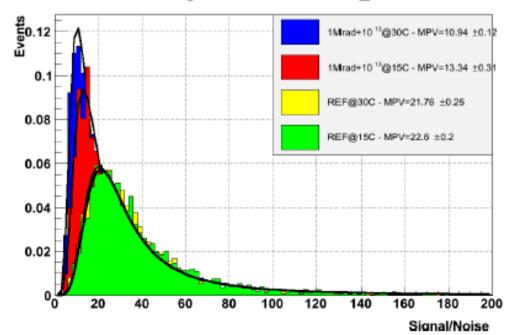
- P9: quadruple well
- L4_1: elongated (20x40 μm²), 1 diode / pixel
- L4_2: elongated (20x40 μm²), 2 diodes / pixel
- Square pixels: S / N, efficiency satisfying for irradiation levels >> ILC environment
 - Elongated pixels: validated for ILC

MIMOSA 32 test beam results (S/N)

Signal/Noise ratio for P9



Signal/Noise ratio for L4_1



P9: Quadruple well

 L4_1: 20x40 μm² dimensions, 1 diode / pixel

Vertex 2012

Summary

- ILD physics program requires a very granular, light vertex detector
 - CMOS sensors technology offers genuinely these qualities
 - Rolling shutter r/o → low power
- But due to beam bkg → swift readout for the inner layers
- **→** Approach for $\sqrt{s} = 500 \text{ GeV}$
 - Based on rolling shutter readout & exploit double sided structure of the ladders
 - Innermost layer
 - > 10 μs time stamping, 3 μm spatial resolution
 - Status
 - MIMOSA 30 tests under way (square & elongated pixels)
 - Double sided ladder tests: late 2012
 - Outer layers
 - Large pixel pitch, spatial resoluiton ~ 3.5 μm
 - Status
 - MIMOSA 31 tests foreseen at beginning 2013
 - ► P_{avg} < 15 W for whole detector (0.35 µm process) \rightarrow air flow cooling

Summary

Approach for √s = 1 TeV

- Move to 0.18 µm process
 - ➤ In pixel discriminator, r/o of multiple rows simultaneously, multiple rolling shutters
 - Time stamping improves by an order of magnitude
 - > 0.18 µm process → less power consumption
- Status
 - MIMOSA 32 under test.
 - First techn. fully adapted to ILC VXD requirements
 - Exhibits satisfactory S/N (≥30), detection ε performances
 - > Even for much higher irradiation level than expected in ILC
 - Resolution measurements under way
 - MIMOSA 32ter submitted
 - MIMOSA 22 THR to be submitted in Dec. 2012
 - AROM 1 @ 2013